

Supporting Information

Piezoresistive and Chemiresistive Gas Sensing by Metal-free Graphene Layers

*Hiroki Kitayama, Mukam Charyyarovich Ekayev, and Tomonori Ohba**

Graduate School of Science, Chiba University, 1-33 Yayoi, Inage, Chiba 263-8522,
Japan

*E-mail: ohba@chiba-u.jp

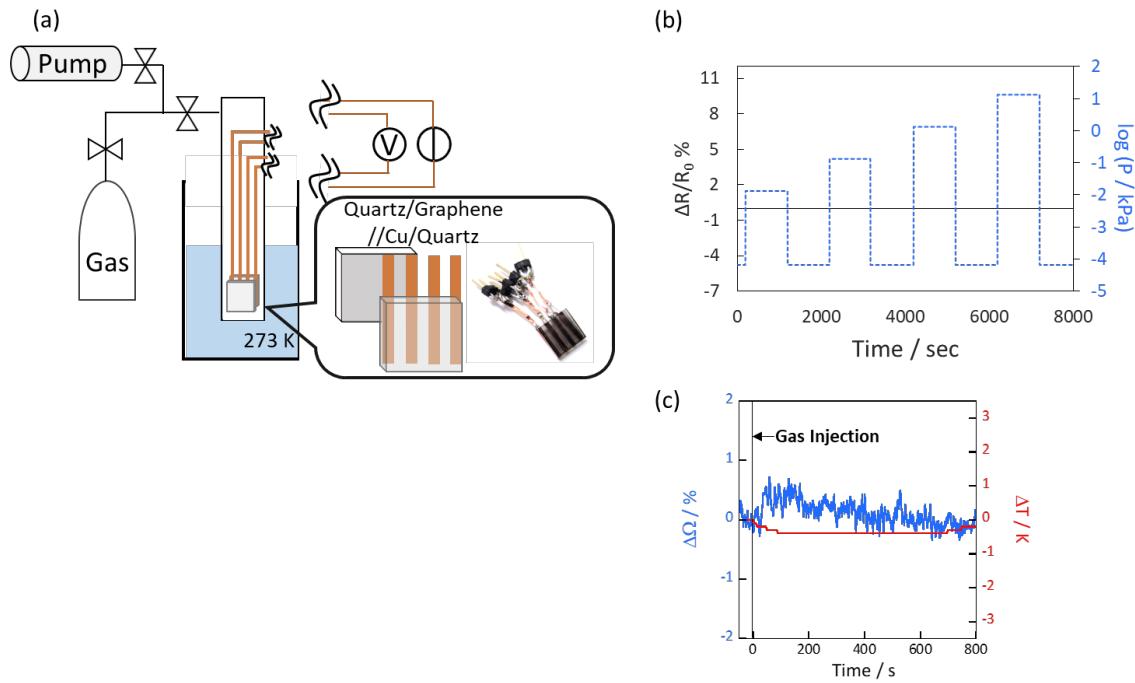


Fig. S1 (a) Image of gas sensing apparatus. (b) Experimental condition of resistance responses by gas injection. (c) Influences of resistance and temperature by He gas injection.

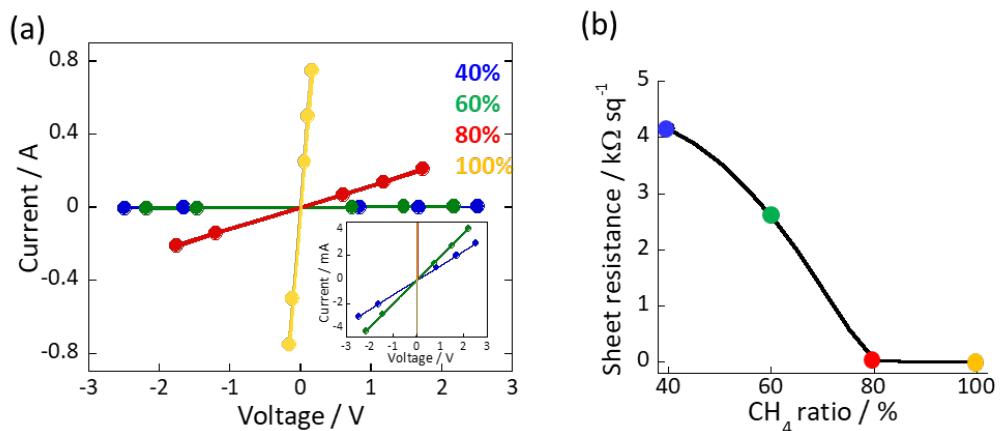


Fig. S2 Current-potential relation (a) and sheet resistance (b) of the GBSs *in vacuo*.

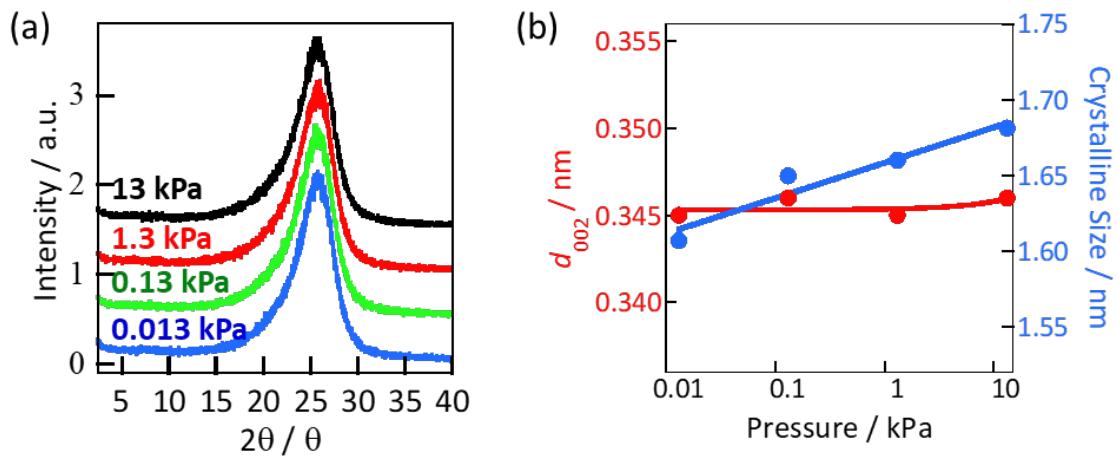


Fig. S3 (a) XRD of GBS of 100% CH₄ ratio. (b) Pressure dependence of crystal structure of GBS for 100% CH₄ ratio at 0–100 kPa. Filled symbol: He gas injection and opened symbol: He gas removal.

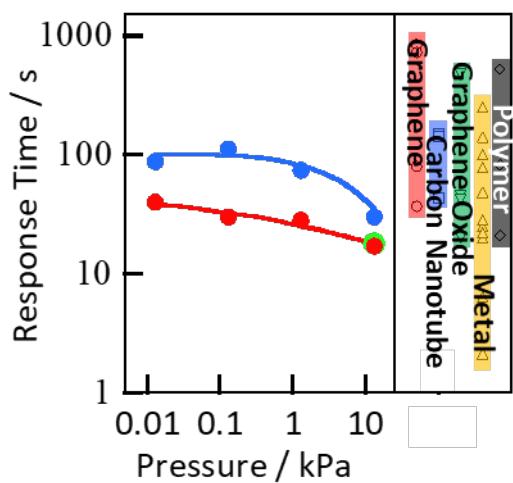


Fig. S4 Response time for NH₃ sensing of GBS by 40% (blue), 60% (green), and 80% CH₄ (red). The response time of other materials was depicted in the right.¹⁻²⁶

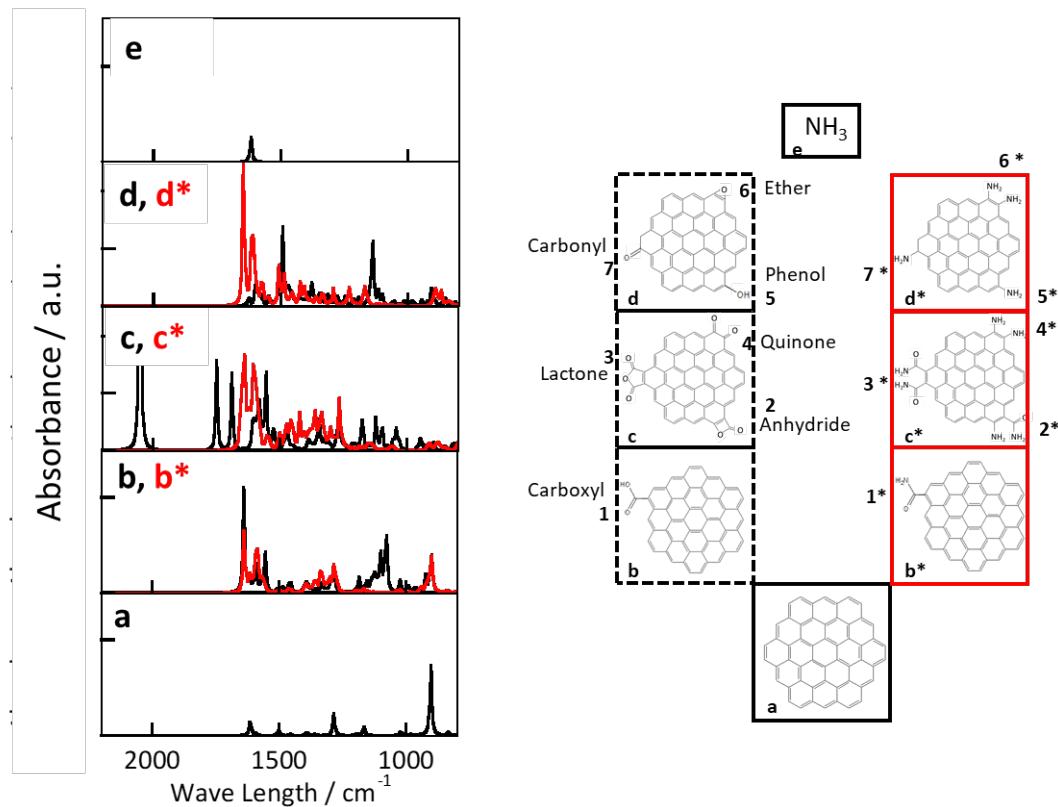


Fig. S5 Calculated absorbance of IR spectra for coronene and coronene derivatives with oxygen and nitrogen atoms (black curves). Solid and dashed curves represent NH_3 chemisorbed-coronene derivatives with oxygen atoms, and coronene derivatives with oxygen atoms, respectively. a: coronene, b: coronene with carboxyl group, b*: coronene with amide bond on carboxyl group, c: coronene with lactone, c*: coronene with amide bond on lactone group, d: coronene with carbonyl group, d*: coronene with amide bond on carbonyl group, and e: NH_3 .

References

1. L. Xue, W. Wang, Y. Guo, G. Liu and P. Wan, *Sens. Actuator B-Chem.*, 2017, 244, 47-53.
2. F. Yavari, E. Castillo, H. Gullapalli, P. M. Ajayan and N. Koratkar, *Appl. Phys. Lett.*, 2012, 100, 203120.
3. J. D. Fowler, M. J. Allen, V. C. Tung, Y. Yang, R. B. Kaner and B. H. Weiller, *ACS Nano*, 2009, 3, 301-306.
4. S. M. Mortazavi Zanjani, M. M. Sadeghi, M. Holt, S. F. Chowdhury, L. Tao and D. Akinwande, *Appl. Phys. Lett.*, 2016, 108, 033106.
5. J. Wu, S. L. Feng, Z. Li, K. Tao, J. Chu, J. M. Miao and L. K. Norford, *Sensor Actuat B-Chem*, 2018, 255, 1805-1813.
6. F. Yan, G. Shen, X. Yang, T. Qi, J. Sun, X. Li and M. Zhang, *Appl. Surf. Sci.*, 2019, 479, 1141-1147.
7. K. Shingange, Z. P. Tshabalala, O. M. Ntwaeborwa, D. E. Motaung and G. H. Mhlongo, *J. Colloid. Interface Sci.*, 2016, 479, 127-138.
8. W. Meng, L. Wang, Y. Li, L. Dai, J. Zhu, H. Zhou and Z. He, *Sens. Actuator B-Chem.*, 2018, 259, 668-676.
9. X. Chen, X. Chen, X. Ding, X. Yu and X. Yu, *Mater. Chem. Phys.*, 2019, 226, 378-386.
10. D. D. Trung, N. D. Cuong, K. Q. Trung, T.-D. Nguyen, N. Van Toan, C. M. Hung and N. V. Hieu, *J. Alloys Compd.*, 2018, 735, 787-794.
11. F. Loghin, A. Abdellah, A. Falco, M. Becherer, P. Lugli and A. Rivadeneyra, *Measurement*, 2019, 136, 323-325.
12. Y. Xiong, W. Xu, D. Ding, W. Lu, L. Zhu, Z. Zhu, Y. Wang and Q. Xue, *J Hazard Mater*, 2018, 341, 159-167.
13. Y. Xiong, Z. Zhu, T. Guo, H. Li and Q. Xue, *J Hazard Mater*, 2018, 353, 290-299.
14. N. V. Toan, C. M. Hung, N. V. Duy, N. D. Hoa, D. T. T. Le and N. V. Hieu, *Materials Science and Engineering: B*, 2017, 224, 163-170.
15. Z. Li, Z. Lin, N. Wang, J. Wang, W. Liu, K. Sun, Y. Q. Fu and Z. Wang, *Sens. Actuator B-Chem.*, 2016, 235, 222-231.
16. J. Sun, X. Shu, Y. Tian, Z. Tong, S. Bai, R. Luo, D. Li and C. C. Liu, *Sens. Actuator B-Chem.*, 2017, 241, 658-664.
17. C. Yu, Y. Wu, X. Liu, F. Fu, Y. Gong, Y.-J. Rao and Y. Chen, *Sens. Actuator B-Chem.*, 2017, 244, 107-113.

18. A. R. Cadore, E. Mania, A. B. Alencar, N. P. Rezende, S. de Oliveira, K. Watanabe, T. Taniguchi, H. Chacham, L. C. Campos and R. G. Lacerda, *Sens. Actuator B-Chem.*, 2018, 266, 438-446.
19. S. Li, T. Wang, Z. Yang, J. He, J. Wang, L. Zhao, H. Lu, T. Tian, F. Liu, P. Sun, X. Yan and G. Lu, *Sens. Actuator B-Chem.*, 2018, 273, 726-734.
20. S. Li, A. Liu, Z. Yang, L. Zhao, J. Wang, F. Liu, R. You, J. He, C. Wang, X. Yan, P. Sun, X. Liang and G. Lu, *Sens. Actuator B-Chem.*, 2019, 289, 252-259.
21. Z. Li, J. Wang, S. Zhang, S. Yan, B. Cao, W. Shen, Z. Wang and Y. Q. Fu, *J. Alloys Compd.*, 2018, 742, 712-720.
22. Y. Huang, L. Wieck and S. Tao, *Atmospheric Environment*, 2013, 66, 1-7.
23. A. M. Al-Enizi, M. Naushad, A. a. H. Al-Muhtaseb, Ruksana, S. M. Alshehri, Z. A. Alothman and T. Ahamad, *Chemical Engineering Journal*, 2018, 345, 58-66.
24. B. Wu, L. Wang, H. Wu, K. Kan, G. Zhang, Y. Xie, Y. Tian, L. Li and K. Shi, *Micropor. Mesopor. Mat.*, 2016, 225, 154-163.
25. S. Kanaparthi and S. G. Singh, *Organic Electronics*, 2019, 68, 108-112.
26. D.-J. Chen, S. Lei, R.-H. Wang, M. Pan and Y.-Q. Chen, *Chinese J. Anal. Chem.*, 2012, 40, 145-149.